

Field-oriented Optimized service



What does it do?

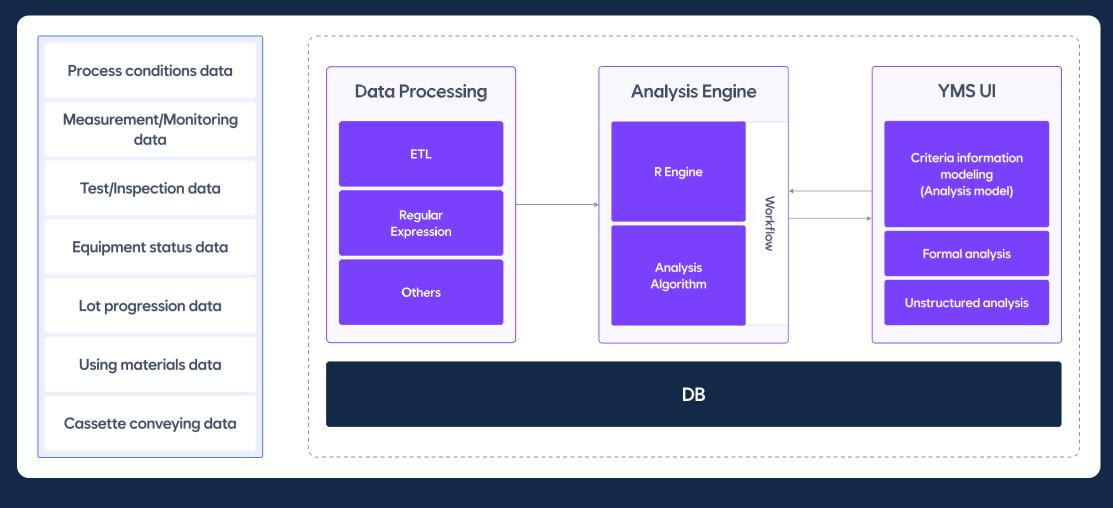
Yield Management System (YMS) leverages all data generated from the manufacturing process to identify potential root causes of issues, such as equipment or process inefficiencies, through structured and unstructured analysis.

- Data analysis: Analyzes data collected during production to detect anomalies and apply statistical methods to improve quality.
- 2. **Real-time monitoring:** Monitors changes in process workflows in real-time, offering early warnings to address problems swiftly.
- **3. Process improvement:** Identifies optimal operating conditions by analyzing correlations between operational parameters and equipment, enhancing process efficiency.
- **4. Data integration:** Consolidates data from various sources to provide a comprehensive view of the environment.

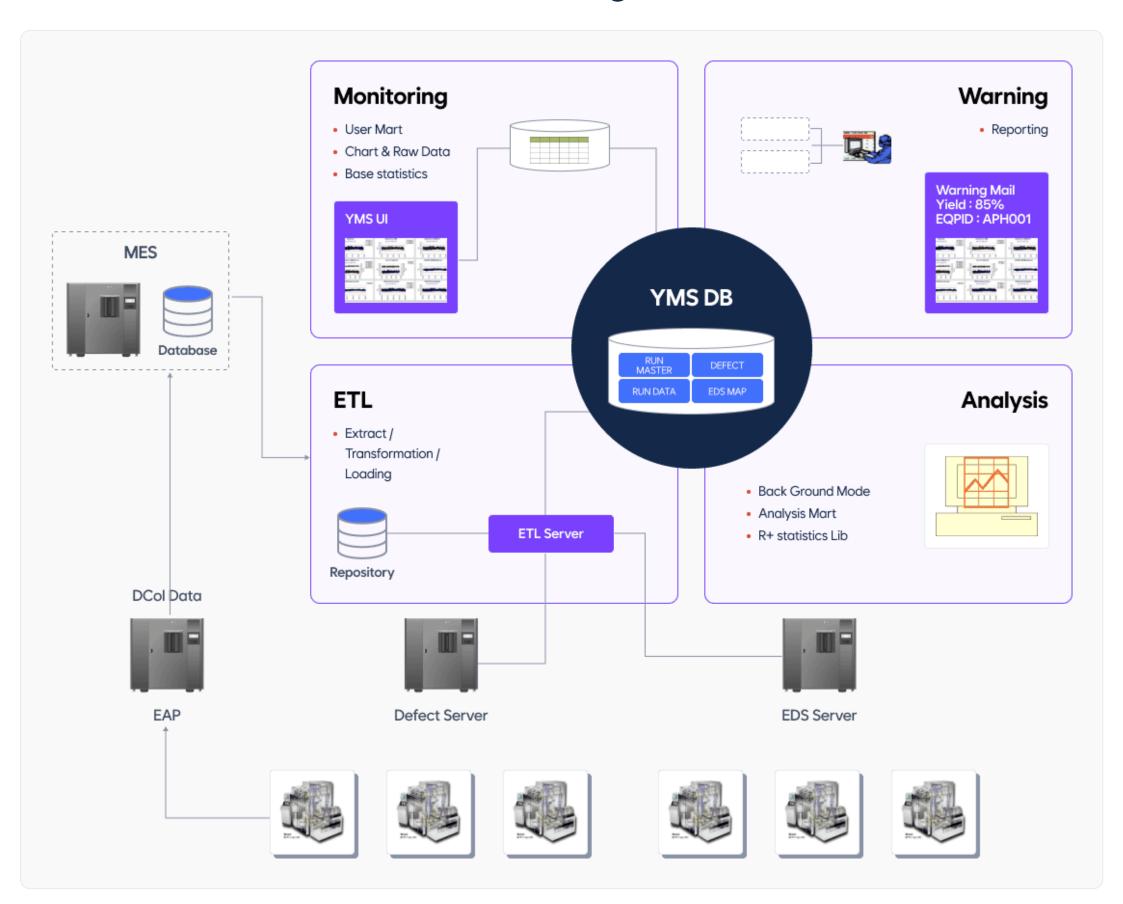
Detects anomalies and analyzes statistical data to improve the quality of manufacturing processes.

Features early warning tools that monitor abnormal signs in real-time process flows.

Provides analytical functions that incorporate variability control and predictive process characteristics.



Product Configuration



Field-oriented Optimized service

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Features early warning tools that monitor abnormal signs in real-time process flows.

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User-friendly

- Open user interface
- Field-oriented system that incorporates engineers' expertise

Data integration

- Comprehensive data integration system for manufacturing processes
- Optimized data network

Standardized analysis process

- Consistent analysis quality without reliance on individual experience
- Eliminates simple and repetitive tasks
- Analytical capabilities enhanced using statistical techniques

Knowledge-based workflows

Workflows that incorporate engineers' expertise

Monitoring

FAB Data Monitoring

- Operation Monitoring
- Equipment Monitoring
- Non-Lot Monitoring (NPW)
- Defect Monitoring
- FAB/Defect Warning

Sort Data Monitoring

- DC/Yield Monitoring
- EDS/PKG Monitoring
- · Outsourcing Monitoring
- DC/EDS Warning

X-Y Monitoring

Field / Raw / Column modify

- Suspected cause factor vs result Monitoring
 - Choose X-Variables, Y-Variables
 - Displaying Trend Chart with Correlation coefficient

Analysis

Yield Analysis

- Bin Map
- Bin Map Gallery
- Cumulative Map
- Compare Map (Before/After Repair)
- Overlay Map (Bin Map vs Defect Map)
- PCM(DC) Shot Map

Defect Analysis

- Defect Map
- Defect Map Gallery
- Defect Image Analysis
- Repeated Defect Analysis
- Defect Pattern Search

Raw Material Analysis

 Ingot/Bare Wafer vs Process / Measurement / Inspection / Test Data Analysis

TOOL

 Lot Trace (Event, Tracking, DC, Material, etc)

Commonality

Traceability

 Equipment Parameter Search (Progress, Significant, EQP path)

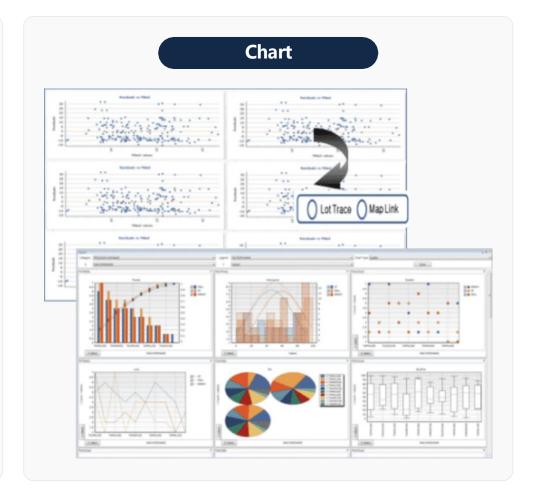
Statistical Analysis

- Data Query (Process, Measurement, PCM, Probe Test Data Query)
- Descriptive Statistics
- Hypothesis Test
- Correlation Analysis
- Regression Analysis
- ANOVA (Analysis of Variance)
- Process Capability Analysis (CP/CPK)
- SPC (Out of Spec, Out of Control Chart & History Data)

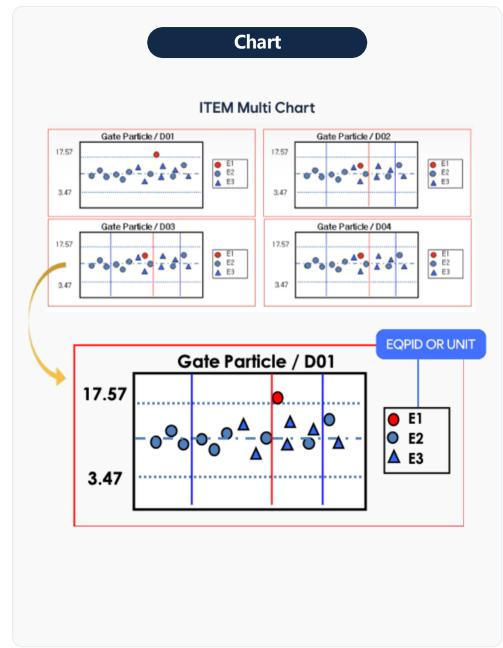
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Search / Output/ Chart / Batch Chart (Line / Data /Pie / Bar / Histogram / Pareto / Box / Correlation Matrix) Lot Link (Trace , Defect Map ,EDS Map)

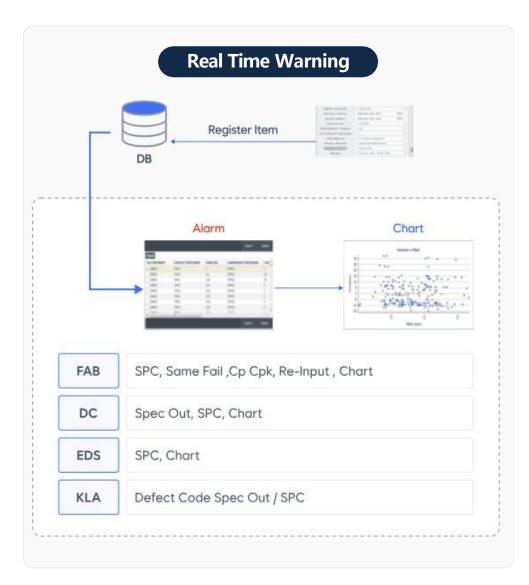
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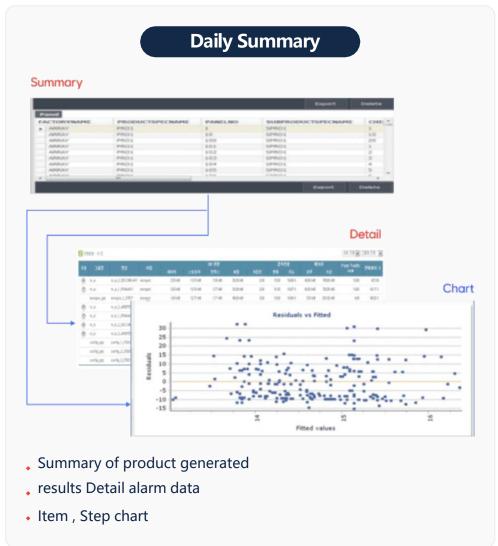




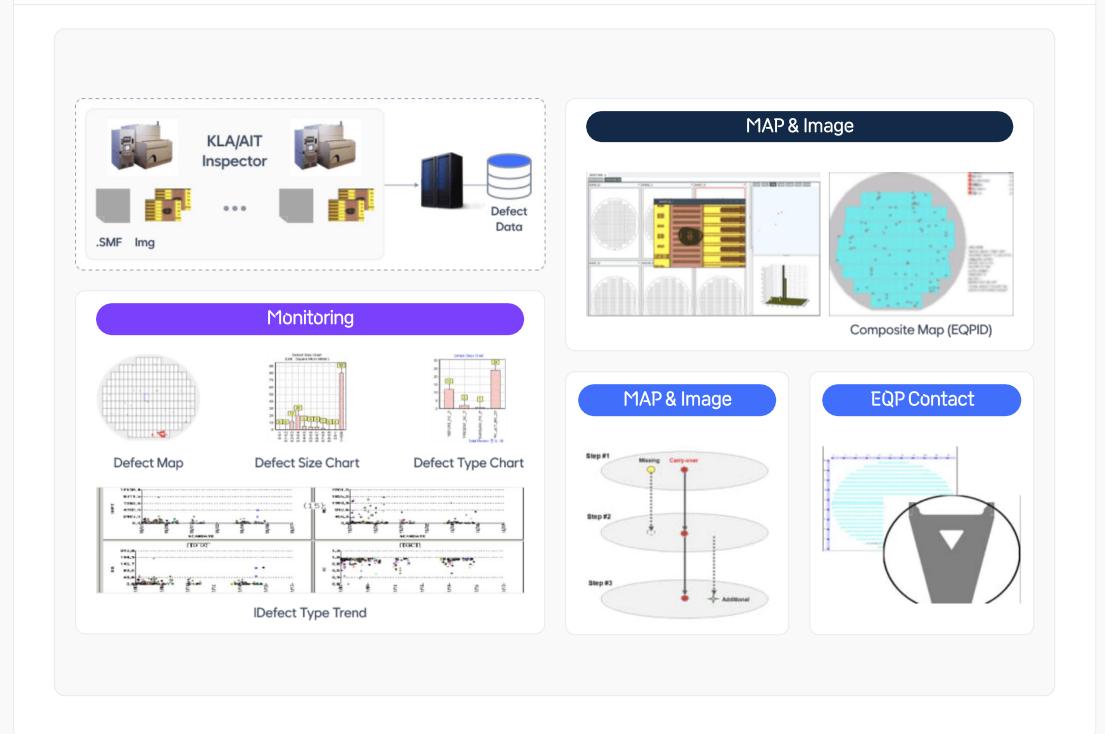


Real Time Warning: Error detection (FAB measurement, DC, EDS data) Daily Summary: Summary of the results of the previous generation

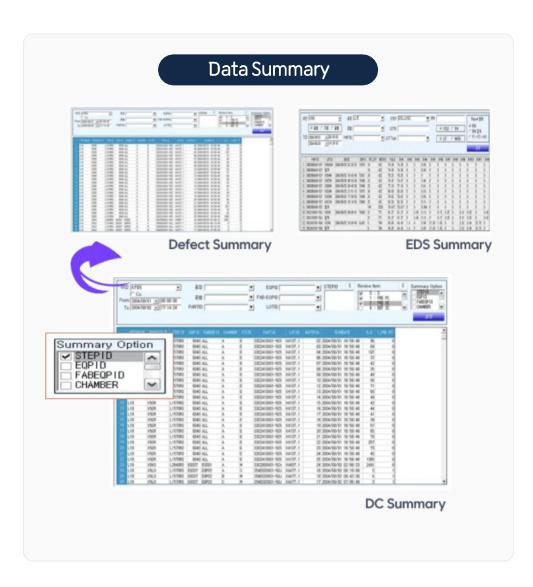


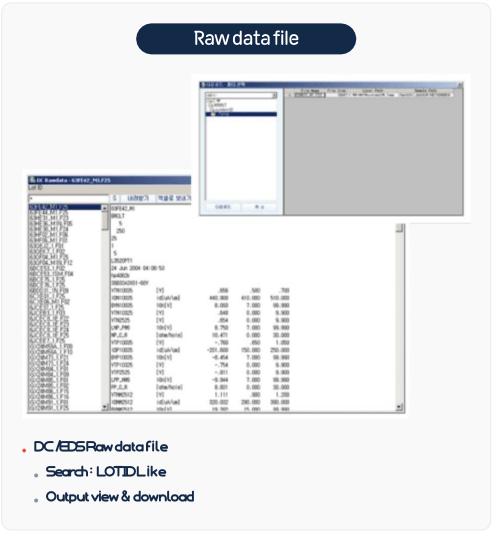






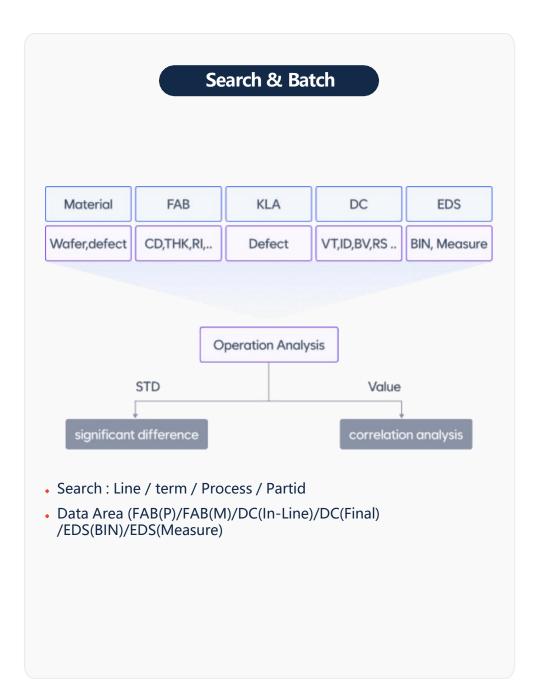
Data Summary: Error detection (FAB measurement, DC, EDS data)
Raw data File: Summary of the results of the previous generation

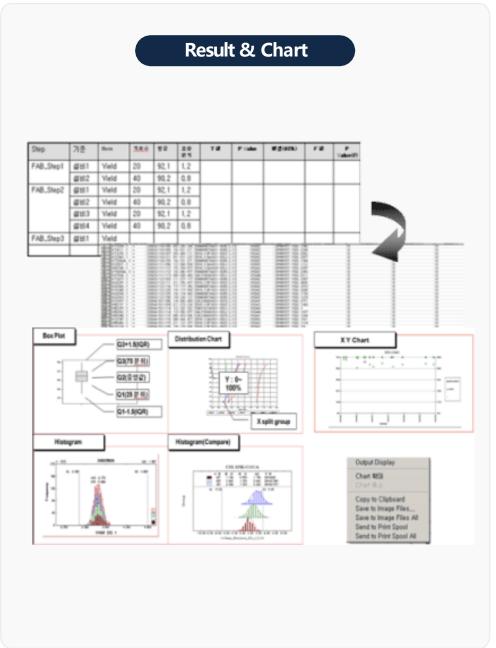




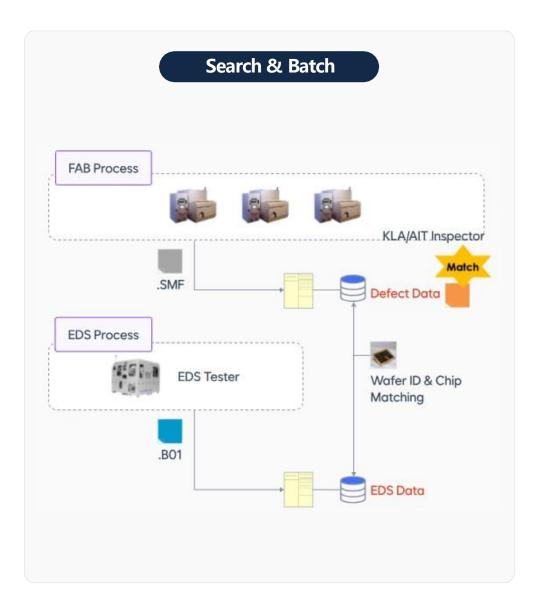
Analysis of significant differences in operational data (EQPID/PPID/Reticle/Probe Card/PartID/Foup)Correlation analysis of operational parameters (CD, THK, VT, BIN, etc.) value Result & Chart (Summary & raw data, Trend, X, Y Chart, Bar Chart, Histogram, Box Plot, Pie Chart)

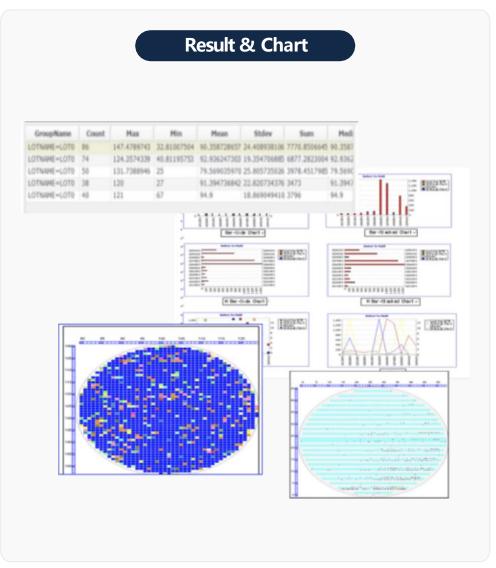
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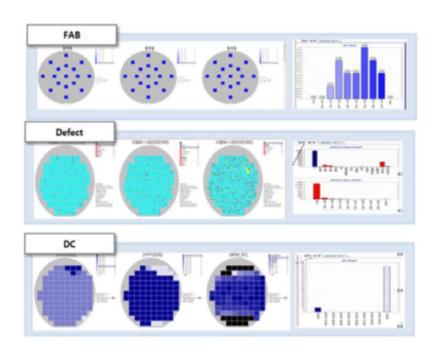




Defect & EDS chip level (BIN, Fail Bit) correlation analysis Defect Class Kill Ratio, Chart (Bar – Side / Bar-Stacked / H Bar–Side / H Bar–Stacked / Scatter / Line), Map







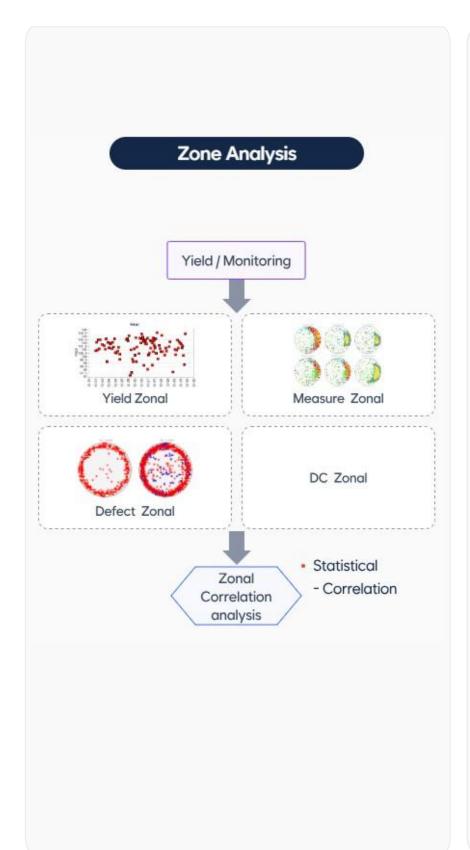
- FAB: Site map, Item Range Bar Chart
- **Defect**: Defect Class, Size Chart, Defect Image
- DC: Item Range Bar Chart

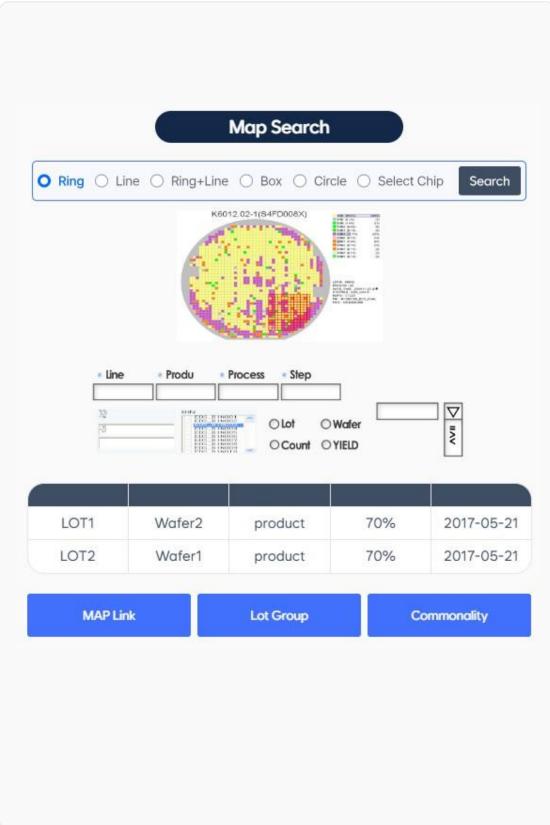
- EDS: BIN, Measure map, BIN, Item Bar Chart
- EDS Map Link : DC . FAB data
- EDS Map Group analysis (AREA, Circle, Shot)

EDA Map Data File (Bin/Measure, Fail Bit) interface Map (Single, Gallery, Composite (Lot, Product, FAB_EQPID, FAP_EQPID_LOT)

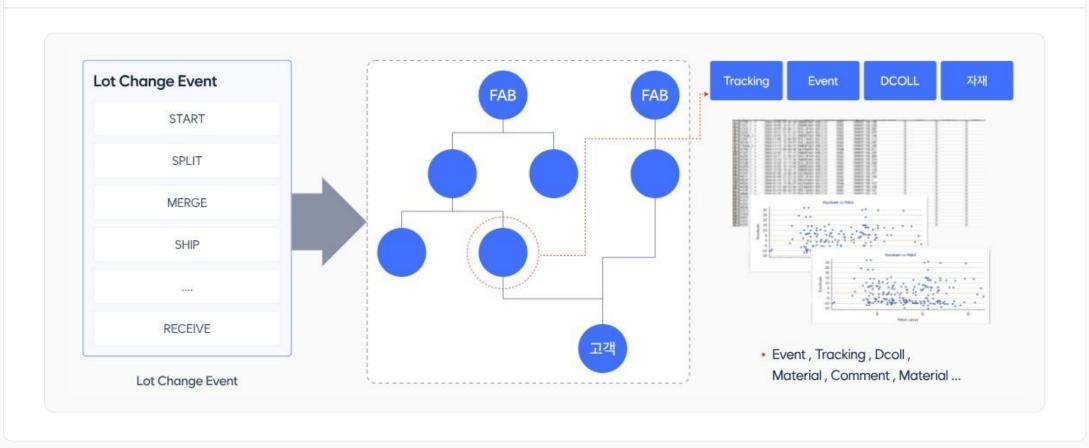




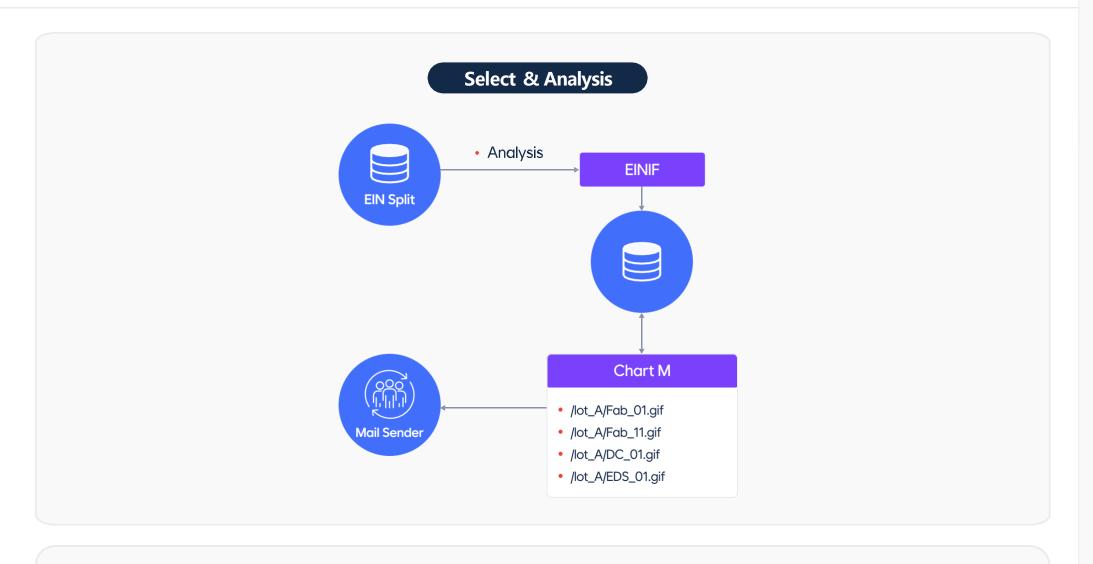




Bi-directional batch tracking and tracingProvides comprehensive information about batches (Events, tracking, FAB (measurements), DC, EDS, material, comments)







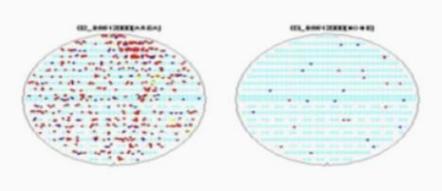


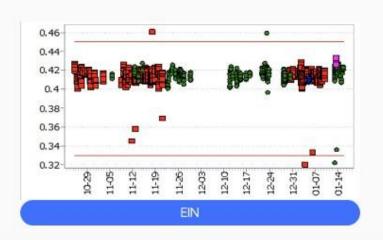
Split Summary FAB DC EDS

PARTID	LOTID	STEP	Wafer ID	DESC	YIELD
S3PART	KOLT.1	150000	#12,1,3,4,6,7,8	NORMAL	91.2
			#2,5,8, 11, 14, 17,20,23	EIN (CP01 CH_B, P-chuck)	90.2

LOTID	STEP	ITEMID	Normal		EIN			P. value	LSL	TARGET	USL	
			CntWF	AVG	STD	CntWF	AVG	STD	r. value	Loc	IAKOLI	OJL
0853.1	6150000	CD1	2	2	0.2	2	2	0.2	0.1	1	2	3

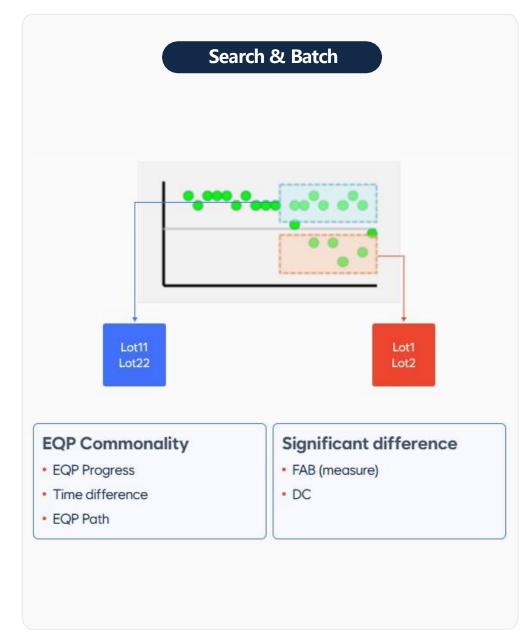
LOTID	STEP	SPLIT Group	0_0	1_PC	2_BG	53_Malbalgub
K0853	2A0076R6	NORMAL	2	11	3	1
K0055	24007010	EIN (CP801 CH_B, P-chuck)	1	2	4	

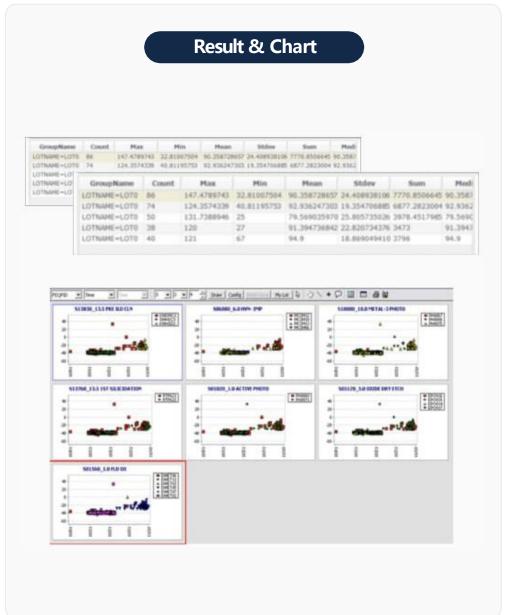




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EQP commonality: Searches for common equipment within defective batch groups. Significant parameter differences: Searches for items (Fab, DC) between two groups (BAD Lot and GOOD Lot)





Search Engine: Enables flexible data access for environmental exploration and unstructured searches. Data Type: FAB (M), FAB(P), EDS Bin, DC, NonLOT, Comment, Material ...



